

UNITED STATES PATENT AND TRADEMARK OFFICE

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BEFORE THE PATENT TRIAL AND APPEAL BOARD

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TAIWAN SEMICONDUCTOR MANUFACTURING COMPANY, LTD. and  
GLOBALFOUNDRIES U.S. INC.,  
Petitioners,

v.

GODO KAISHA IP BRIDGE 1,  
Patent Owner.

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Case No. IPR2016-01376<sup>1</sup>  
Patent Number 6,197,696

Before JUSTIN T. ARBES, MICHAEL J. FITZPATRICK, and  
JENNIFER MEYER CHAGNON, *Administrative Patent Judges*.

**PATENT OWNER'S UPDATED LIST OF EXHIBITS**

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<sup>1</sup> GlobalFoundries U.S. Inc., who filed Petition IPR2017-00921, has been joined as a petitioner in this proceeding.

In accordance with 37 C.F.R. § 42.63(e), Patent Owner Godo Kaisha IP Bridge 1 (“Patent Owner”) hereby submits a current listing of Patent Owner’s exhibits.

**List of Exhibits**

<b>Exhibit</b>	<b>Description</b>	<b>Previously Filed</b>
EX2001	N. Sclater & J. Markus, McGraw-Hill Electronics Dictionary (6th ed. 1997) (excerpted)	x
EX2002	R. F. Graf, Modern Dictionary of Electronics (6th ed. 1984) (excerpted)	x
EX2003	R. F. Graf, Modern Dictionary of Electronics (7th ed. 1999) (excerpted)	x
EX2004	S. M. Kaplan, Wiley Electrical and Electronics Engineering Dictionary (2004) (excerpted)	x
EX2005	October 7, 2016 Preliminary Constructions, <i>Godo Kaisha IP Bridge 1 v. Broadcom Ltd., et al.</i> , (E.D. Tex 2:16-CV-134-JRG-RSP)	x
EX2006	Declaration of Seung Woo Hur	x
EX2007	RESERVED	
EX2008	RESERVED	
EX2009	Declaration of Alexander Glew, Ph.D. In Support of Patent Owner’s Response Under 37 C.F. R. § 42.120	x
EX2010	Deposition of Bruce Smith in <i>Taiwan Semiconductor Manufacturing Co., v. Godo Kaisha IP Bridge 1</i> (P.T.A.B. IPR2016-01376) taken on March 23, 2017	x
EX2011	Redline Comparing Grill (EX1005) with Grill’s Provisional (EX1017) Application	x
EX2012	Japanese Patent Application 10-079371 to Aoi as Submitted in European Patent Application No. 99 105 946.0 with accompanying translation	x
EX2013	Declaration of Takeo Ohashi, Ph.D. In Support of Patent Owner’s Response Under 37 C.F. R. § 42.120	x
EX2014	<i>Influence of reactor wall conditions on etch processes in inductively coupled fluorocarbon plasmas</i> by M.	x

	Schaepkens, et al., J. Vac. Sci. Tech. A 16(4), Jul/Aug 1998	
EX2015	<i>Handbook of VLSI Microlithography, Second Edition, Principles, Technology, and Applications</i> , edited by John N. Helbert, Noyes Publications, William Andrew Publishing, LLC, 2001	x
EX2016	<i>Silicon VLSI Technology Fundamentals, Practice and Modeling</i> , by James D. Plummer, et al., Prentice Hall, 2000	x
EX2017	<i>Microlithography: Science and Technology</i> , by James R. Sheats and Bruce W. Smith, Marcel Dekker, Inc., 1998	x
EX2018	<i>Microlithography: Science and Technology</i> , 2 <sup>nd</sup> ed., by James R. Sheats and Bruce W. Smith, CRC Press, 2007	x
EX2019	<i>Microlithography: Science and Technology</i> , 2 <sup>nd</sup> ed., by James R. Sheats and Bruce W. Smith, CRC Press, 2007	x
EX2020	<i>Silicon Processing for The VLSI Era Vol. 2 Process Integration</i> by Stanley Wolf and R.N. Tauber, Lattice Press, 1986	x
EX2021	Kenkyusha's New Japanese-English Dictionary, 4 <sup>th</sup> ed., 35 <sup>th</sup> Impression, published by Kenkyusha Ltd., 1997	x
EX2022	Declaration of Jordan M. Rossen In Support of Patent Owner's Response Under 37 C.F. R. § 42.120	x
EX2023	Declaration of Susann Brailey and Exhibit A regarding <i>Influence of reactor wall conditions on etch processes in inductively coupled fluorocarbon plasmas</i> by M. Schaepkens, et al., J. Vac. Sci. Tech. A 16(4), Jul/Aug 1998	Served only.
EX2024	Affidavit of Pamela Stansbury regarding <i>Influence of reactor wall conditions on etch processes in inductively coupled fluorocarbon plasmas</i> by M. Schaepkens, et al., J. Vac. Sci. Tech. A 16(4), Jul/Aug 1998	Served only.
EX2025	<i>Influence of reactor wall conditions on etch processes in inductively coupled fluorocarbon plasmas</i> by M. Schaepkens, et al., J. Vac. Sci. Tech. A 16(4), Jul/Aug 1998	Served only.
EX2026	Library of Congress Certification of <i>Handbook of VLSI Microlithography, Second Edition, Principles, Technology, and Applications</i> , edited by John N.	Served only.

	Helbert, Noyes Publications, William Andrew Publishing, LLC, 2001 (excerpted)	
EX2027	Library of Congress Certification of <i>Handbook of VLSI Microlithography, Principles, Technology, and Applications</i> , edited by William B. Glendinning and John N. Helbert, Noyes Publications, William Andrew Publishing, LLC, 1991 (excerpted)	Served only.
EX2028	Library of Congress Certification of <i>Silicon VLSI Technology Fundamentals, Practice and Modeling</i> , by James D. Plummer, et al., Prentice Hall, 2000 (excerpted)	Served only.
EX2029	Affidavit of Pamela Stansbury regarding <i>Silicon VLSI Technology Fundamentals, Practice and Modeling</i> , by James D. Plummer, et al., Prentice Hall, 2000	Served only.
EX2030	<i>Silicon VLSI Technology Fundamentals, Practice and Modeling</i> , by James D. Plummer, et al., Prentice Hall, 2000 (excerpted)	Served only.
EX2031	Library of Congress Certification of <i>Microlithography: Science and Technology</i> , by James R. Sheats and Bruce W. Smith, Marcel Dekker, Inc., 1998 (excerpted)	Served only.
EX2032	Library of Congress Certification of <i>Microlithography: Science and Technology</i> , 2 <sup>nd</sup> ed., by Kazuaki Suzuki and Bruce W. Smith, CRC Press, 2007 (Chapter 12) (excerpted) (Smith Deposition Exhibit 3)	Served only.
EX2033	Library of Congress Certification of <i>Microlithography: Science and Technology</i> , 2 <sup>nd</sup> ed., by Kazuaki Suzuki and Bruce W. Smith, CRC Press, 2007 (Chapter 11) (excerpted) (Smith Deposition Exhibit 9)	Served only.
EX2034	Affidavit of Pamela Stansbury regarding <i>Silicon Processing for The VLSI Era Vol. 1 Process Technology</i> by Stanley Wolf and R.N. Tauber, Lattice Press, 1986	Served only.
EX2035	<i>Silicon Processing for The VLSI Era Vol. 1 Process Technology</i> by Stanley Wolf and R.N. Tauber, Lattice Press, 1986 (excerpted)	Served only.
EX2036	U.S. Pat. No. 5,322,749	Served only.
EX2037	U.S. Pat. No. 6,181,420	Served only.

EX2038	U.S. Pat. No. 6,808,647	Served only.
EX2039	Declaration of Jordan M. Rossen	Served only.
EX2040	Transcript of the Deposition of Dr. B. Smith (August 2, 2017)	

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